

IN RE APPLICATION OF:

ATSUSHI SHIOTA ET AL.

: GROUP ART UNIT: 1712

SERIAL NO: 09/770,289

: EXAMINER: FEELY, M.

FILED: JANUARY 29, 2001

: RCE FILED: HEREWITH

FOR: PROCESS FOR PRODUCING

SILICA-BASED FILM, SILICA-

BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE

AMENDMENT

COMMISSIONER FOR PATENTS ALEXANDRIA, VA 22313-1450

SIR:

Further to the Request for Continued Examination filed herewith, and in response to the Final Rejection dated June 9, 2003, please amend the application identified above as follows.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.

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RESPONSE

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313-1450

SIR:

In response to the Office Action dated December 9, 2003, and in accordance with Examiner Feely's instructions during the telephone conference of December 11, 2003, attached is a copy of the Amendment filed October 9, 2003, and a copy of the date-stamped filing receipt. The Amendment filed October 9, 2003, included Claim 6.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND, MAIER & NEUSTADT, P.C.

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